

Supplementary Information for

Single reactor deposition of silicon/tungsten oxide  
core-shell heterostructure nanowires with  
controllable structure and optical properties

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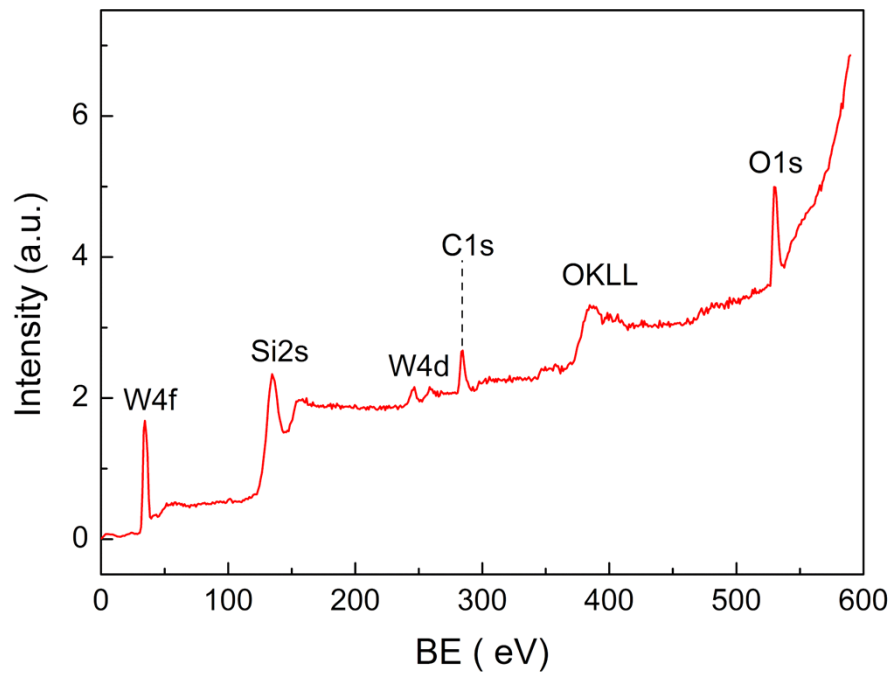


Figure S1 typical XPS spectrum of the Si/WO<sub>3</sub> core-shell NWs.

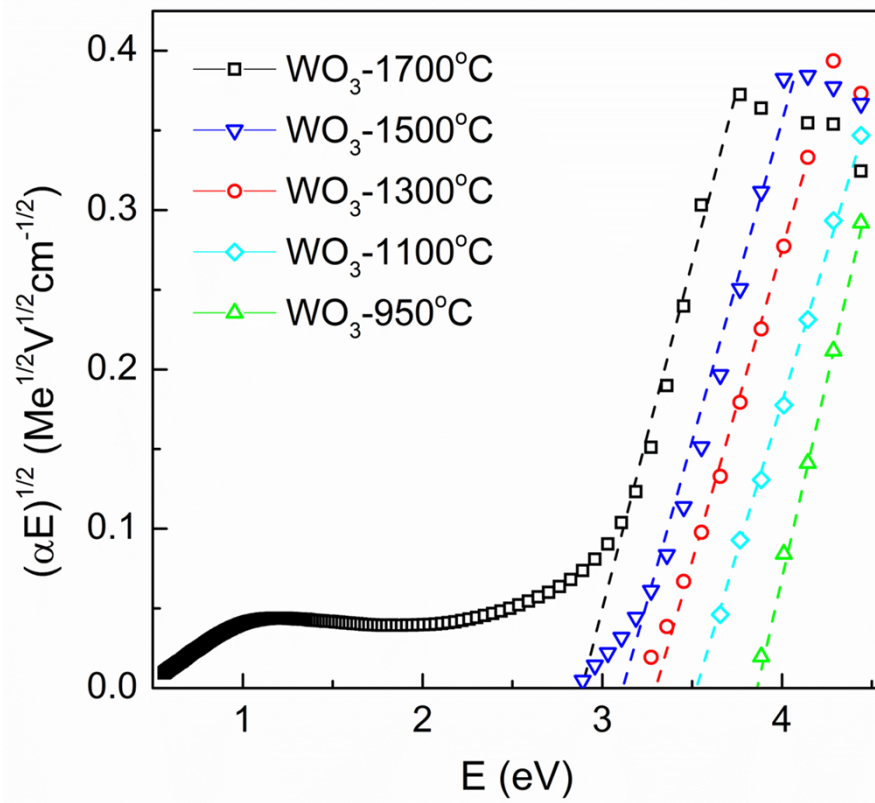


Figure S2 Tauc's plots of the  $\text{WO}_3$  thin films prepared at different  $T_f$ .

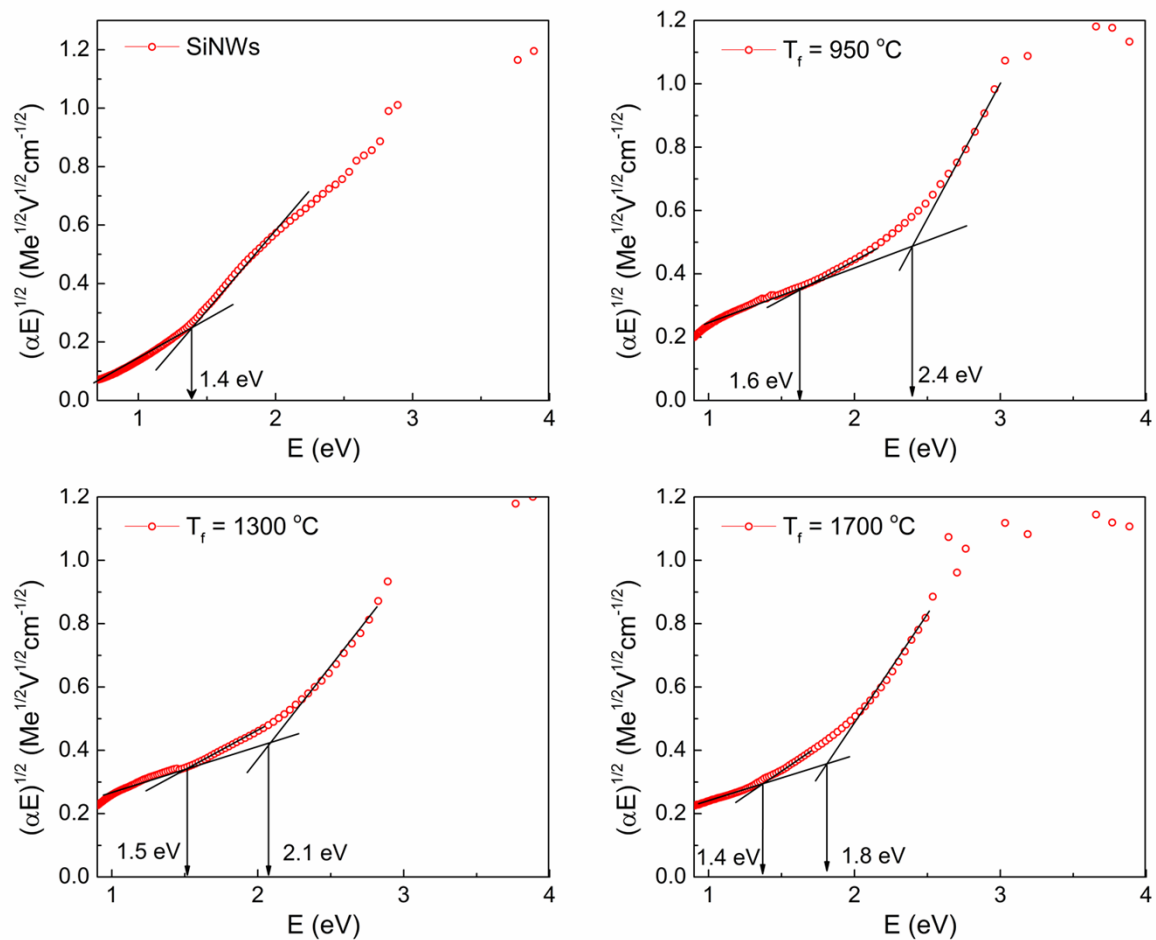


Figure S3 Tauc's plots of Si NWs, and Si/WO<sub>3</sub> core-shell NWs prepared at different  $T_f$ . The Tauc's plots of the Si/WO<sub>3</sub> core-shell NWs revealed the indirect optical band gap of both Si (lower energy) core and WO<sub>3</sub> (higher energy) shell.

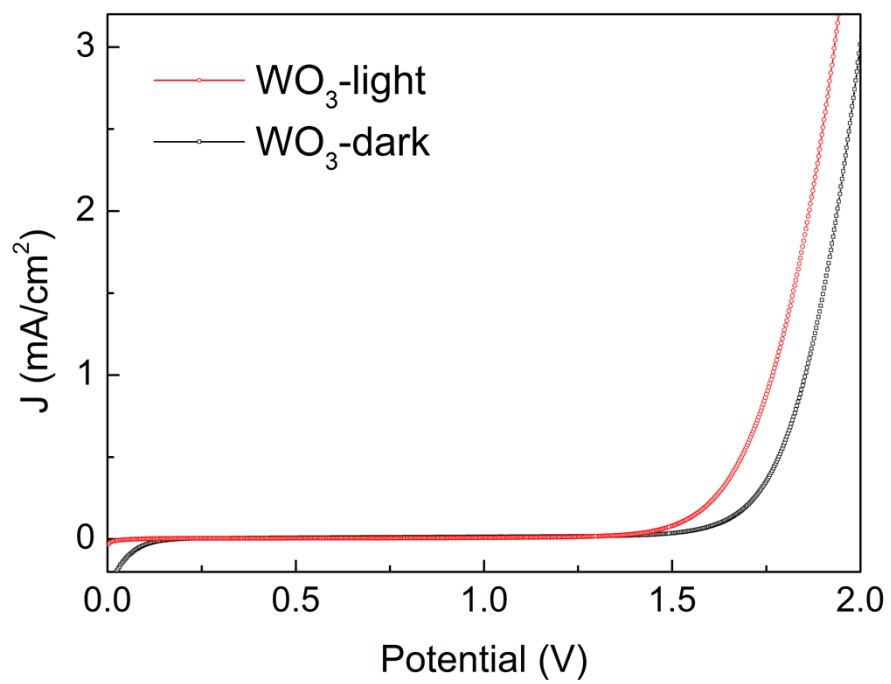


Figure S4 Typical current density versus potential plots of the WO<sub>3</sub> films under dark and illumination.

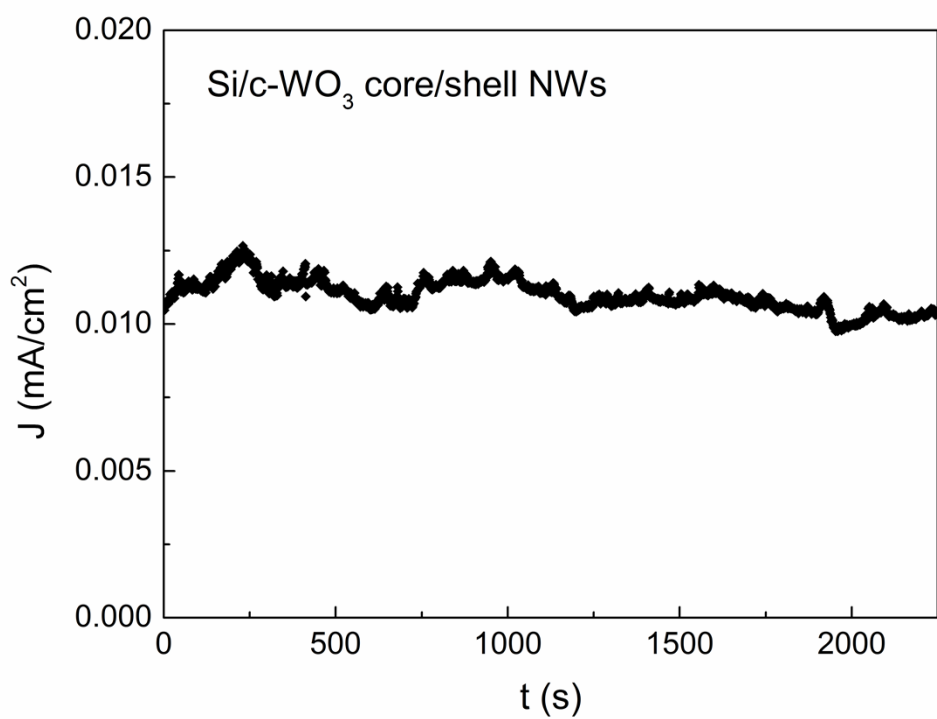


Figure S5 Photocurrent density versus time plot of the Si/crystalline WO<sub>3</sub> core-shell NWs.